

Form PTO 1449 (Modified)		U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE		ATTY DOCKET NO. <b>245583US0S DIV</b>		SERIAL NO. <b>New Application</b>	
LIST OF REFERENCES CITED BY APPLICANT				APPLICANT <b>Satoshi MATSUDA, et al.</b>			
				FILING DATE <b>Herewith</b>		GROUP	
<b>U.S. PATENT DOCUMENTS</b>							
EXAMINER INITIAL	DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS	FILING DATE IF APPROPRIATE	
<i>JH</i>	AA	6,518,155	02-03	CHAU, ET AL.			
<i>JH</i>	AB	6,573,583	06-03	HOKAZONO			
<i>JH</i>	AC	6,127,707	10-00	CHONG, ET AL.			
	AD						
	AE						
	AF						
	AG						
	AH						
	AI						
	AJ						
	AK						
	AL						
	AM						
	AN						
<b>FOREIGN PATENT DOCUMENTS</b>							
		DOCUMENT NUMBER	DATE	COUNTRY	TRANSLATION		
					YES	NO	
<i>JH</i>	AO	411274320A	10-99	JAPAN			
<i>JH</i>	AP	2002-110817	04-02	JAPAN			X
	AQ						
	AR						
	AS						
	AT						
	AU						
	AV						
<b>OTHER REFERENCES (Including Author, Title, Date, Pertinent Pages, etc.)</b>							
<i>JH</i>	AW	Yasuhiro SATO, et al., "Study of HF-Treated Heavily-Doped Si Surface Using Contact Angle Measurements", JPN. J. APPL. PHYS., Volume 33, December 1994, Pages 6508-6513.					
<i>JH</i>	AX	Toshihiko KOSUGI, et al., "Effects of Hydrogenation of Hydrogen Termination of p <sup>+</sup> -silicon (100) Surfaces by Hydrofluoric Acid", J. VAC. SCI. TECHNOL. A15(1), Jan/Feb 1997, Pages 127-132.					
<i>JH</i>	AY	Yoshihiro SUGITA, et al., "Influence of Microscopic Chemical Reactions on the Preparation of an Oxide-Free Silicon Surface in a Fluorine-Based Solution", JPN. J. APPL. PHYS., Volume 38, 1999, Pages 2427-2433.					
	AZ						
					<input type="checkbox"/> Additional References sheet(s) attached		
Examiner <i>Gymne A. Hurley</i>					Date Considered <i>9/3/04</i>		
*Examiner: Initial if reference is considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.							